

ABSTRACT

PROCESS FOR MAKING A THIN FILM BY APPLYING PRESSURE

- 5 The invention relates to a process for making a
thin film starting from a substrate (1) of a solid
material with a plane face (2) comprising:
- the implantation of gaseous compounds in the substrate
 (1) to make a layer of micro-cavities (4) at a depth
10 from the said plane face (2) corresponding to the
thickness of the required thin film, the gaseous
compounds being implanted under conditions that could
weaken the substrate at the layer of micro-cavities,
 - partial or total separation of the thin film from the
15 rest of the substrate (1), this separation comprising a
step in which thermal energy is added and pressure is
applied to the said plane face (2).

Figure 2